

FIG.1A(Prior Art)

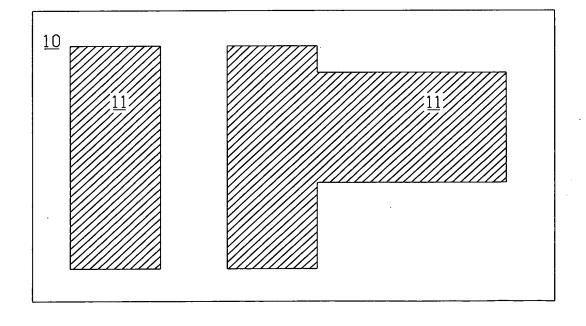


FIG.1B(Prior Art)

TITLE: METHOD FOR REDUCING LINE EDGE ROUGHNESS PHOTORESIST Inventor: Yen-Ting LU
Docket No. 4425-168

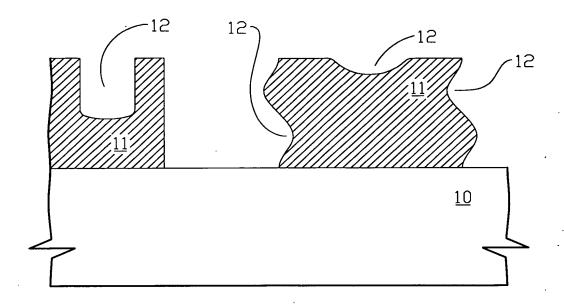


FIG.1C(Prior Art)

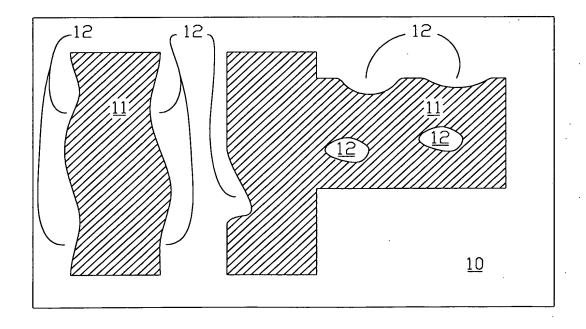


FIG.1D(Prior Art)

Inventor: Yen-Ting LU Docket No. 4425-168

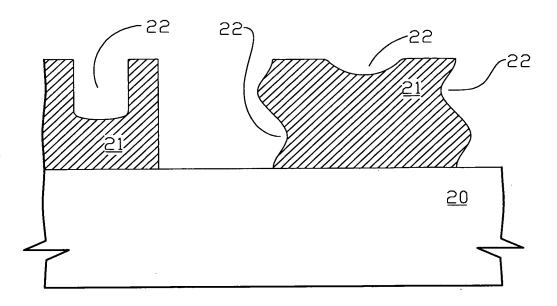


FIG.2A

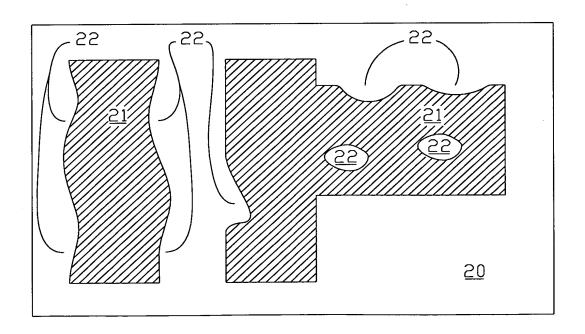


FIG.2B

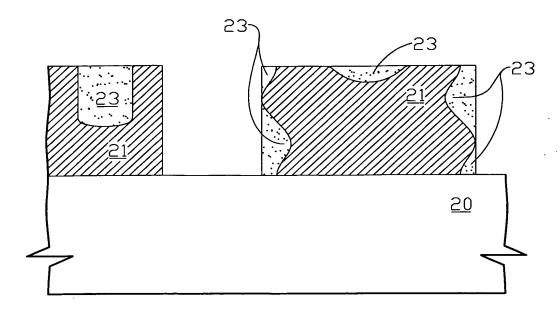


FIG.2C

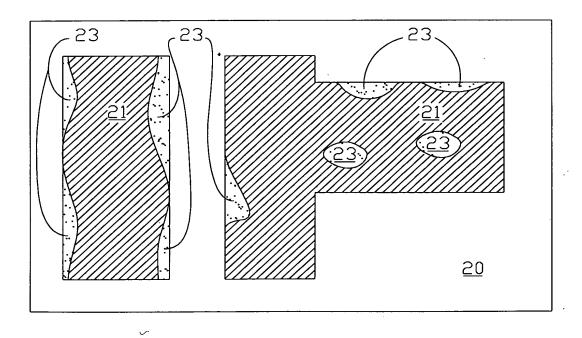


FIG.2D

Fill trenches to let trenches be totally filled by additional material.

Treat additional material to let that adhesion between additional material and photoresist be enhanced after additional material is treated.

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Treat additional material and photoresist be enhanced after additional material is treated.

FIG.3A

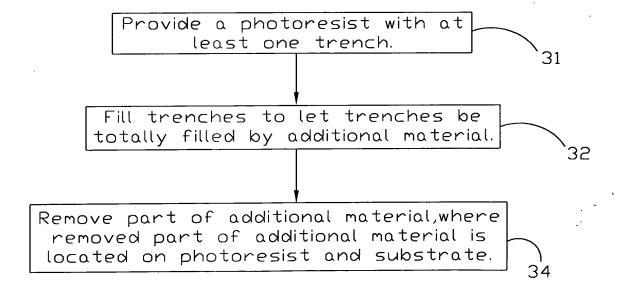


FIG.3B

FIG.3C

COLUMN: BORNING